Recipe for photoresist AZnLof 2020 LSW

Application

AZ® nLOF 2000 is a series of negative resists, whereby the exposed resist remains after development with an adjustable undercut. The negative profile in combination with its high softening point makes AZ® nLOF 2000 a well-suited resist for lift-off as well as for any other processes requiring resist structures with high to very high thermal stability.

Process

Tone	**Negative**
Reference	Photoresist AZ nLof 2020 Photoresists MicroChemicals GmbH
Spin coat	3,5 um @4000 RPM
Pre bake	90s @100 °C
Exposure time HBG_uMLA	Dose 95 focus +4
Post exposure bake	135s @110 °C
Development	MF322 for 150s
Stopping of development	30s in water then rinse it with water

Kavli Nanolab Delft
Enabling nanodevice fabrication

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